

Innovative ultra-**BRO**adband ubiquitous **Wireless** communications through terahertz transceivers **iBROW**

Mar-2017



- Project key facts
- Motivation
- Project objectives
- Project technology
 - RTDs
 - RTDs on silicon
 - User scenarios
- Summary

- Horizon 2020 project funded by the European Commission
 - ICT-6: Smart optical and wireless network technologies
- Budget: c. 4 M€
- Eleven partners
 - 2 large industrial, 3 SME, 3 R&D, 3 academic
- Start date: 01-Jan-2015
- Duration: 36 months
- Coordinator: University of Glasgow
- Project public website: www.ibrow-project.eu



Academic

RTD research (device & circuit design, process development)

NOKIA Bell Labs



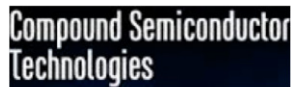
Large Industrial

Component manufacturer (optical/wireless network equipment)



R&D

III-V on Si wafer bonding research



SME

Component manufacturer (III-V based devices)



R&D

III-V on Si research (design, processing and validation)



R&D

Wireless/optical communications research



Large Industrial

Wafer manufacturing (III-V on Si epitaxial growth)



SME

Component manufacture (packaging solutions)



Academic

mm-wave & THz wireless communications research



Academic

RTD research (design, modelling and characterisation)



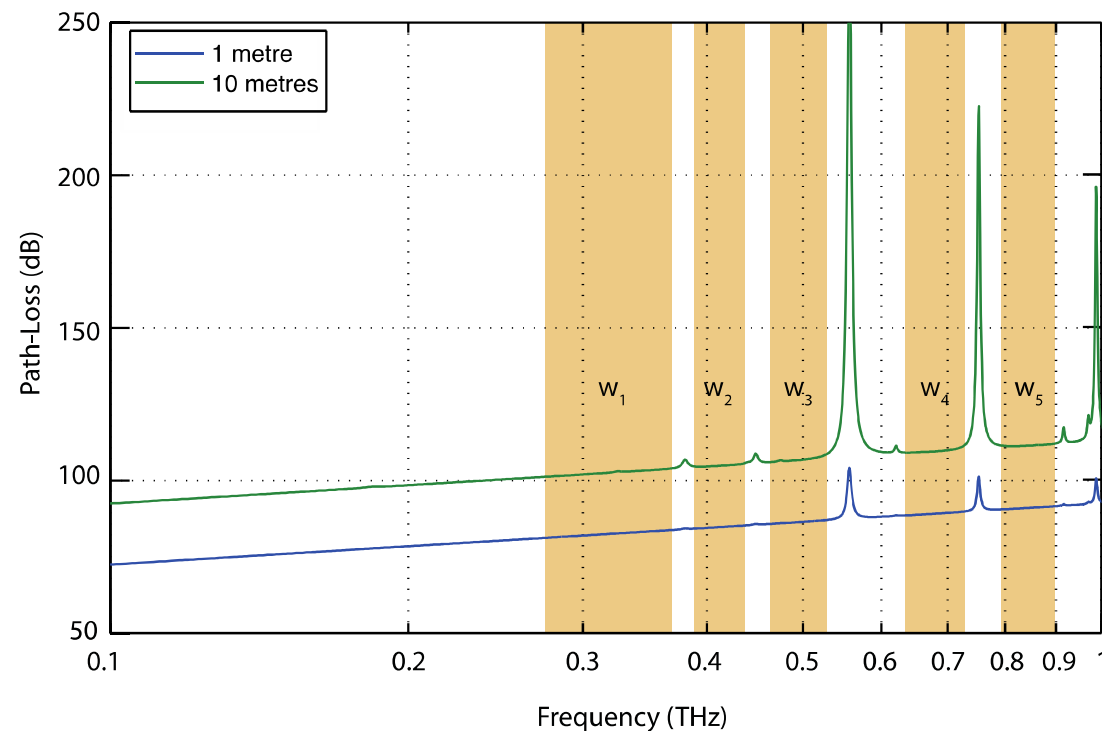
SME

Project management

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- Traffic from wireless devices soon expected to exceed that from wired devices
- High-resolution video will account for 69% of all mobile data by 2018, up from about 53% in 2013
- Wireless data-rates of multiple tens of Gbps will be required by 2020
- Demand on short-range connectivity

- Significant previous R&D effort in complex modulations, MIMO and DSP up to 60 GHz
- Spectral Efficiency (SE) limits
 - Achieving 10s of Gbps in current bands will require high SE



→ Solution?

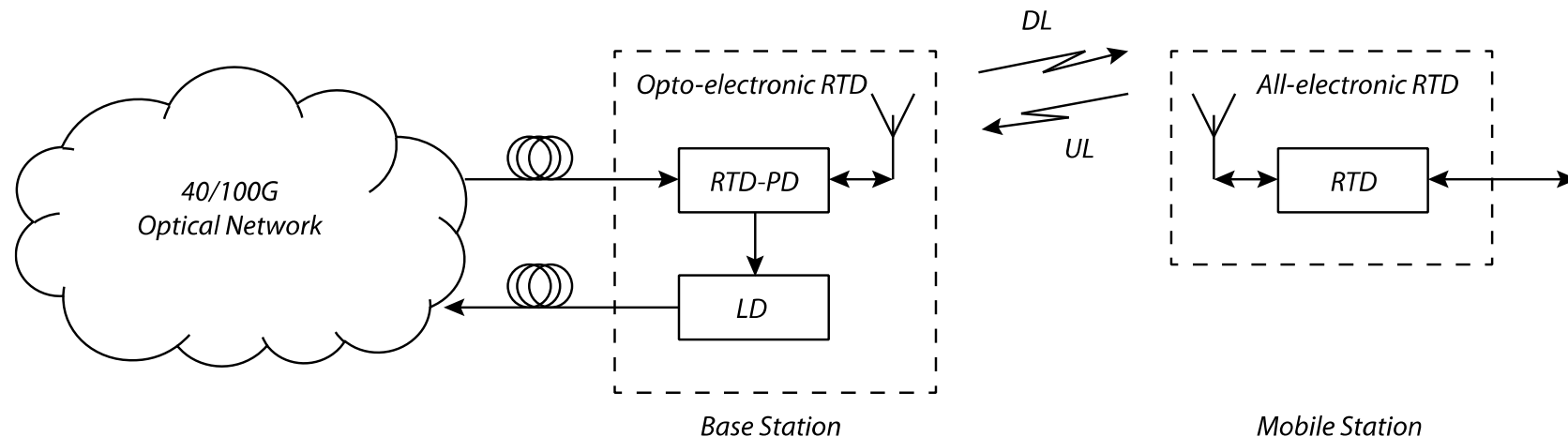
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Develop a novel short range wireless communication transceiver technology that is:

- Energy-efficient
- Compact
- Ultra-broadband
- Seamlessly interfaced with optical fibre networks
- Capable of addressing predicted future network usage needs and requirements.

- Demonstrate **low cost and simple** wireless transceiver architectures that can achieve at least **10 Gbps** by exploiting the mm-wave and THz frequency spectrum
 - Long term target **100 Gbps**.
- Demonstrate **integrated semiconductor** emitters & detectors having enough power/sensitivity for exploiting the full potential of THz spectrum, and allowing for **seamless fibre-wireless interfaces**.
- Demonstrate a **highly compact** technology suitable for integration into battery constrained **portable devices**.
- Develop an **energy efficient and low power** wireless communications technology addressing the reduction of the ICT carbon footprint imputed to communication networks.

- Exploit Resonant Tunnelling Diode (RTD) transceiver technology



- All-electronic RTD for integration into cost-effective wireless portable devices
- Opto-electronic RTD (RTD-PD-LD) for integration into mm-wave/THz femtocell basestations

- Baseline studies to establish application scenarios
 - RTD technology options
 - Channel modelling & communications architectures
- Monolithic realisation of high power
 - 10 mW @ 90 GHz
 - 1 mW @ 300 GHz
 - Low phase noise sources

→ Ultimately on a III-V on Si platform
- Monolithic realisation of high responsivity (>0.6 A/W) and high sensitivity RTD-photodiode detectors
- Hybrid integration of RTD-PD and laser diode optical-wireless interface and its characterisation
- Evaluation of wireless-wireless links and optical-wireless links
- Test bed demonstrator

Consortium organisation

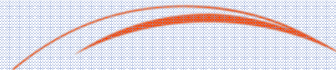
Electronic RTD design



III-V on silicon



III-V lab



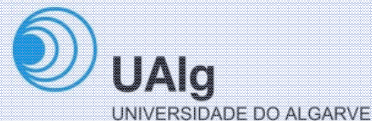
Packaging

optocap

Communications



Optoelectronic RTD Design



Compound Semiconductor Technologies

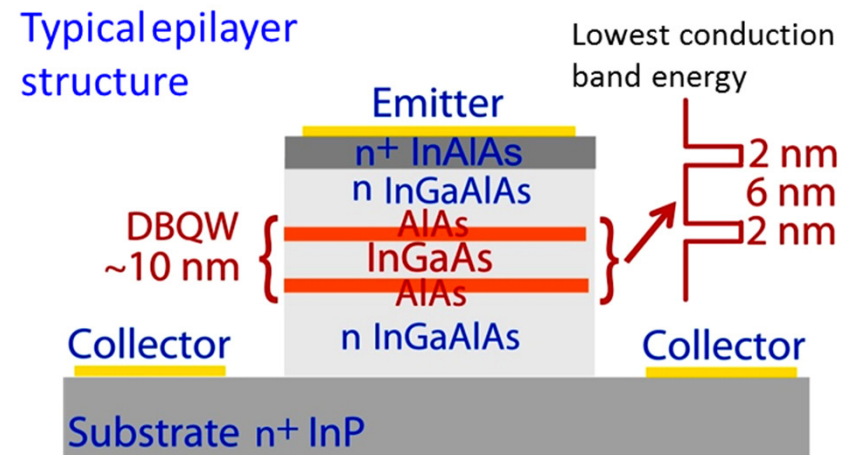
End-User

NOKIA Bell Labs

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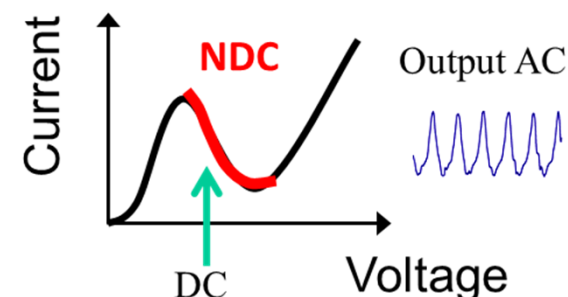
What is an RTD?

- RTD first demonstrated in 1974
- Consists of vertical stacking of nanometric epitaxial layers of semiconductor alloys forming a double barrier quantum well (DBQW)
- Oscillations can be controlled by either electrical or optical signals
- Highly nonlinear device
 - Complex behaviour including chaos
- Exhibit wideband negative differential conductance (NDC)

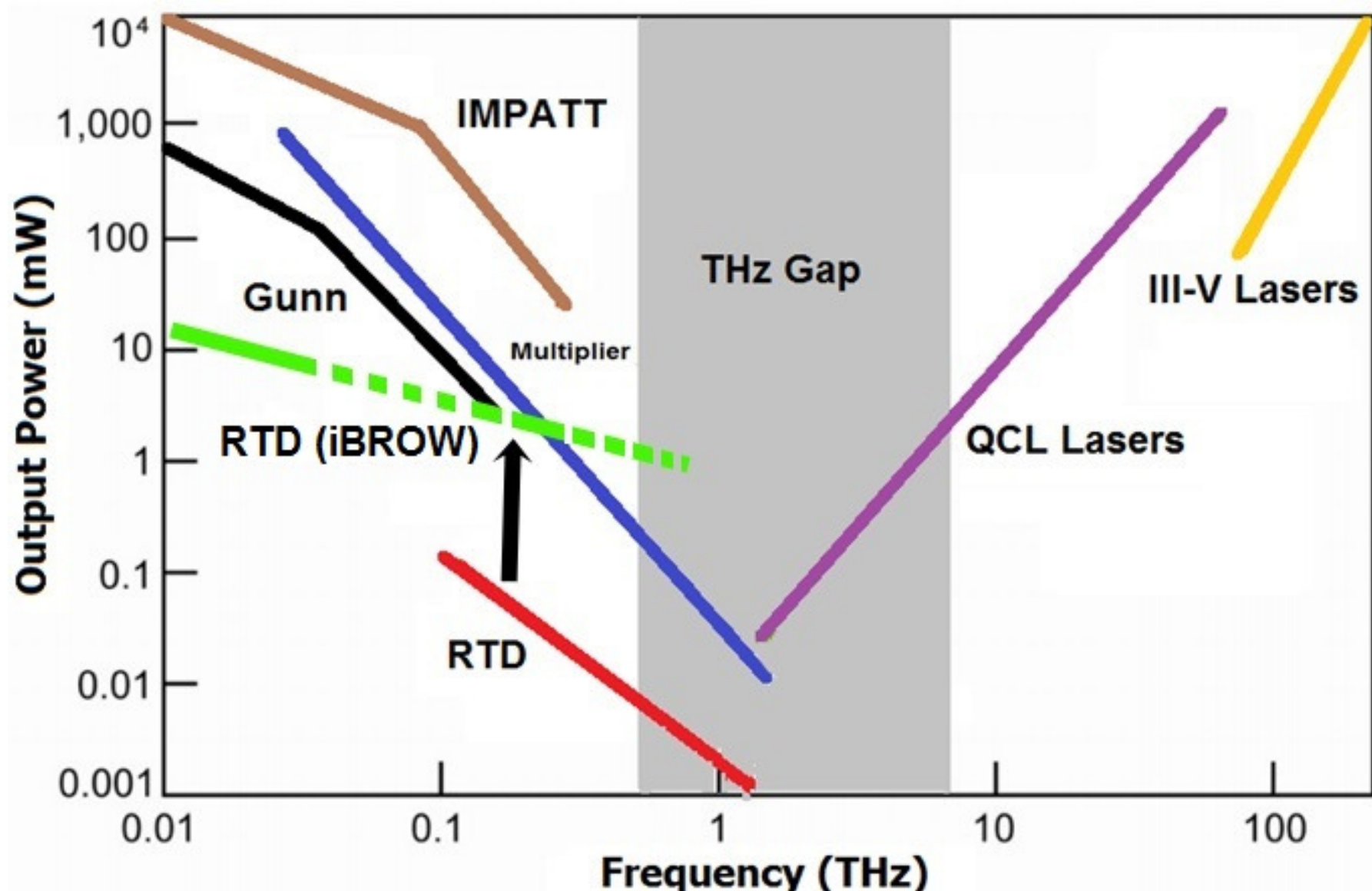


Current-Voltage (I-V) curve

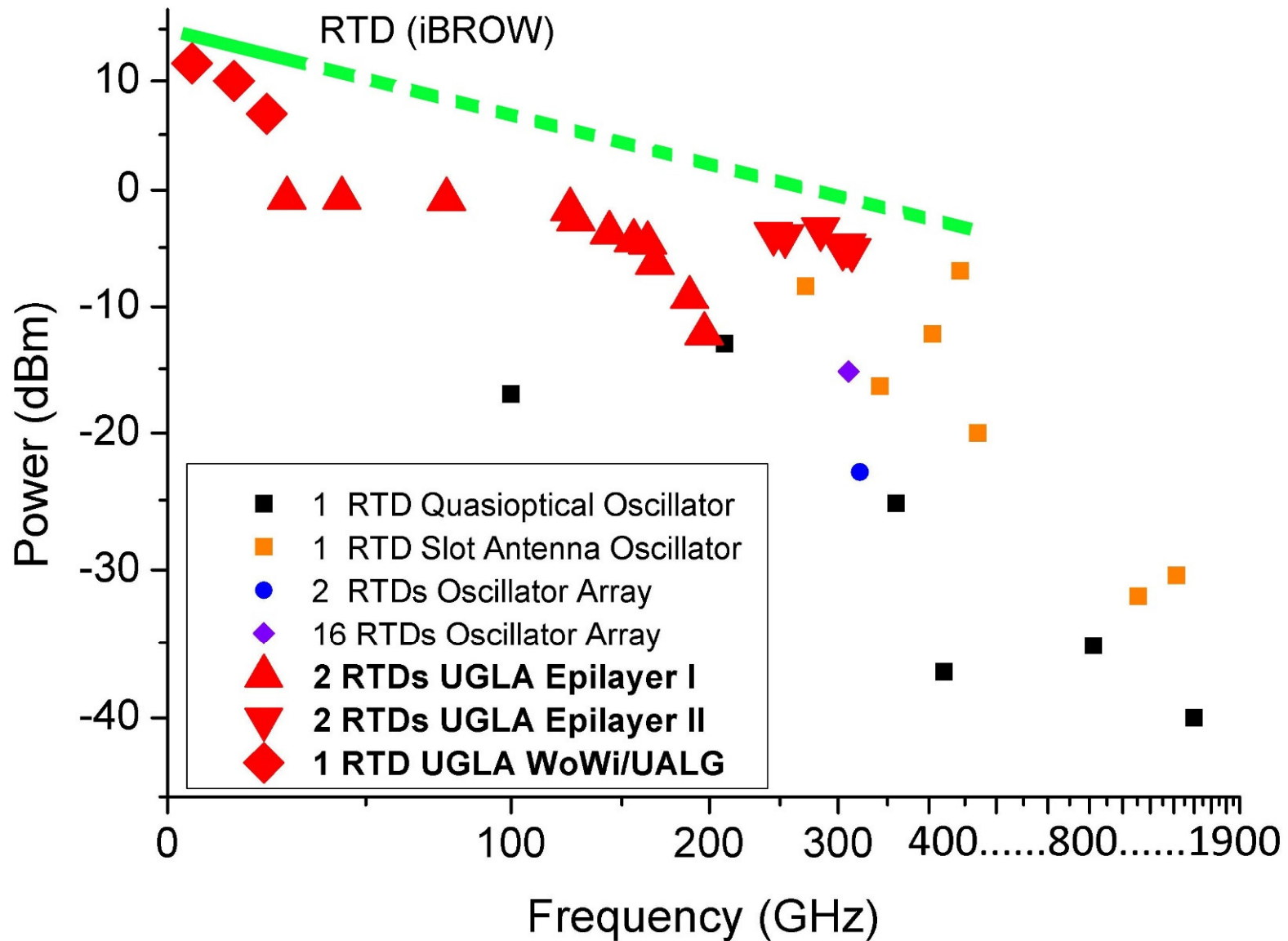
(NDC – Negative Differential Conductance)



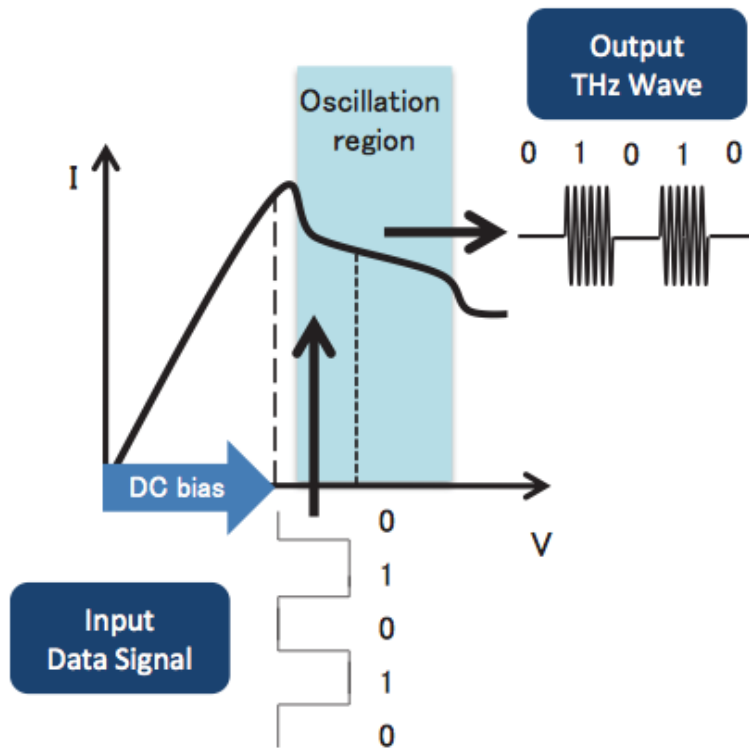
RTDs vs Other Technologies



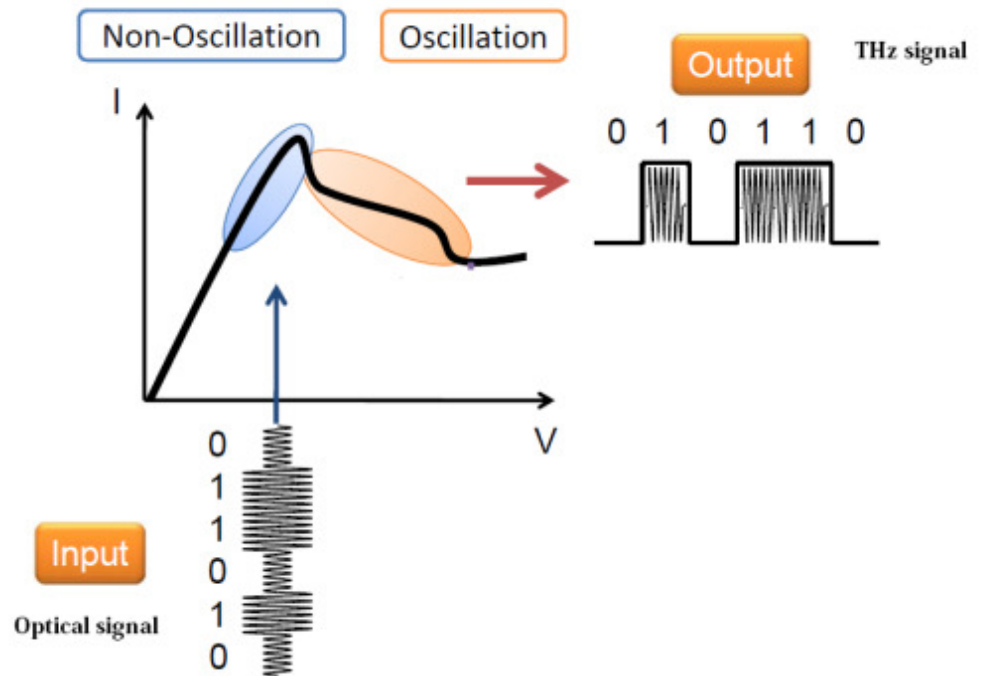
State-of-the-art RTDs



Taking advantage of RTD-based communications: On-off keying modulation

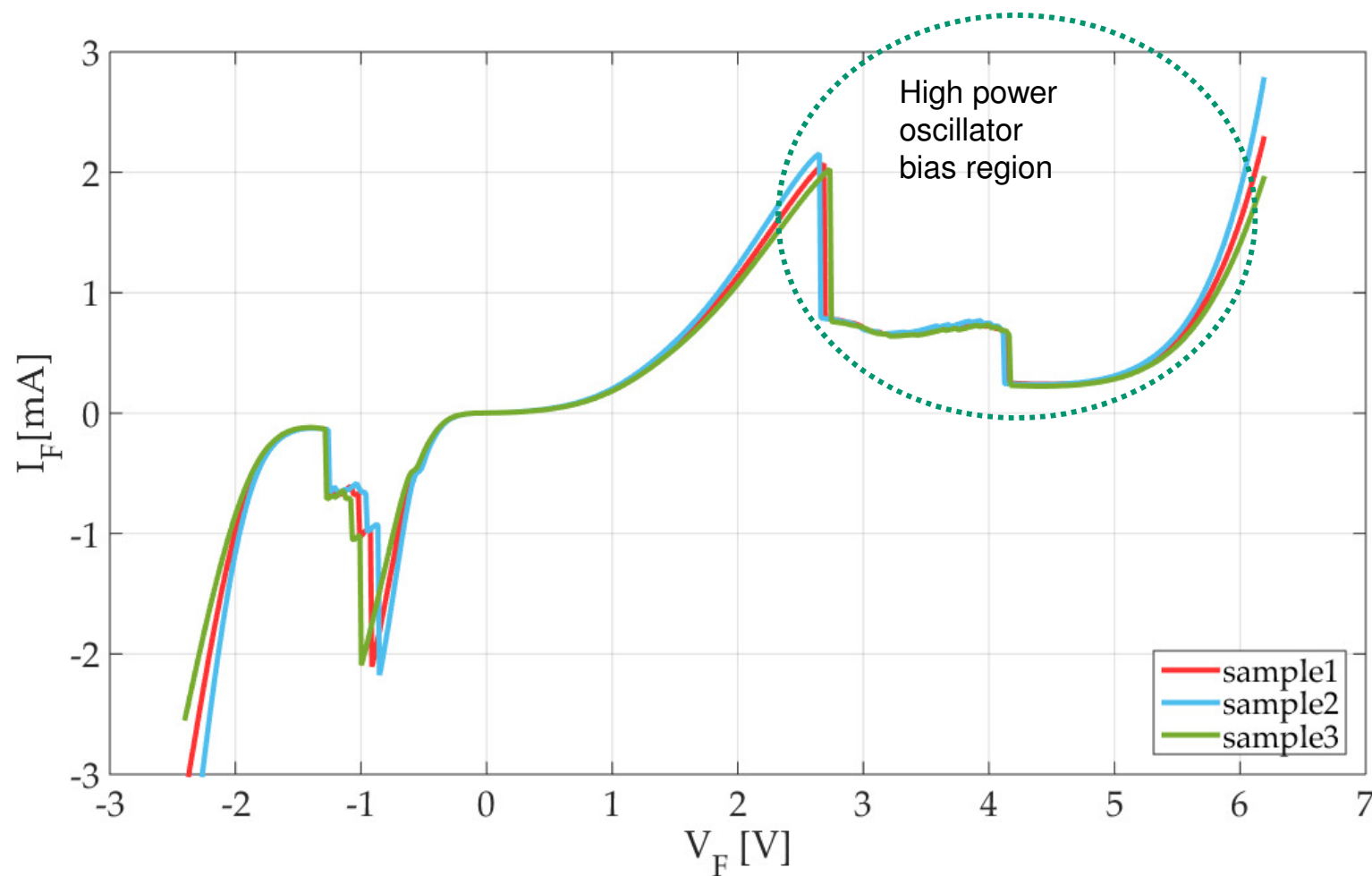


- All-electronic RTD

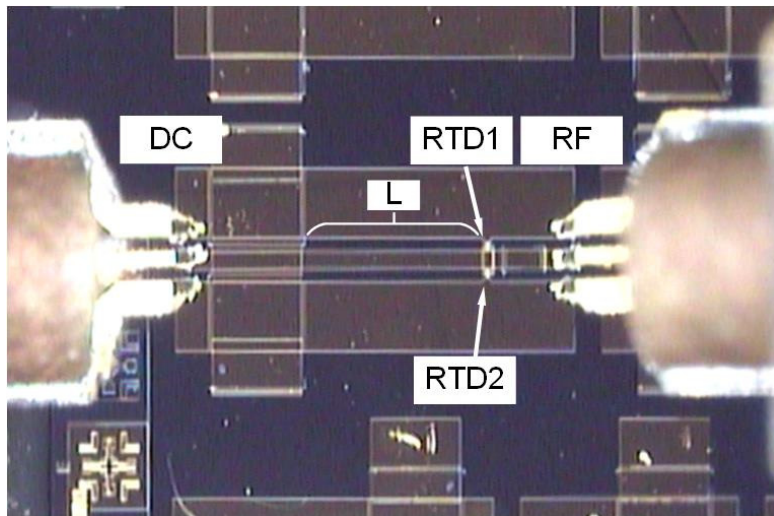
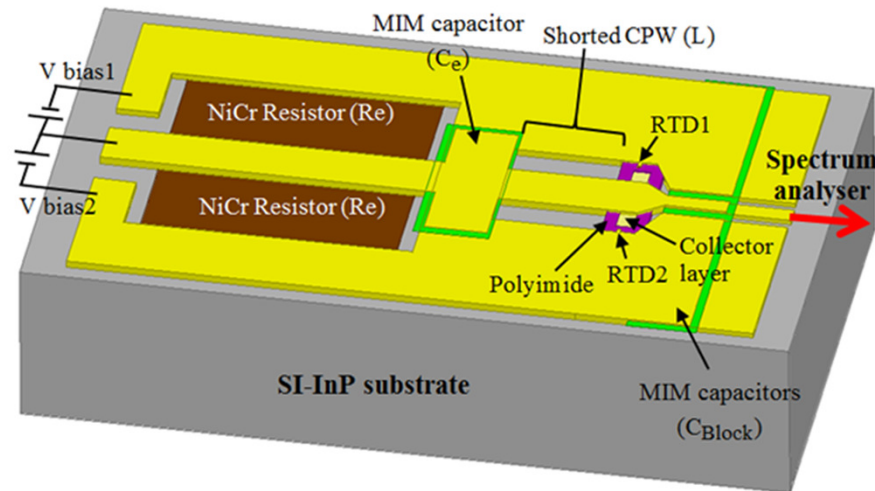


- Optoelectronic RTD-PD

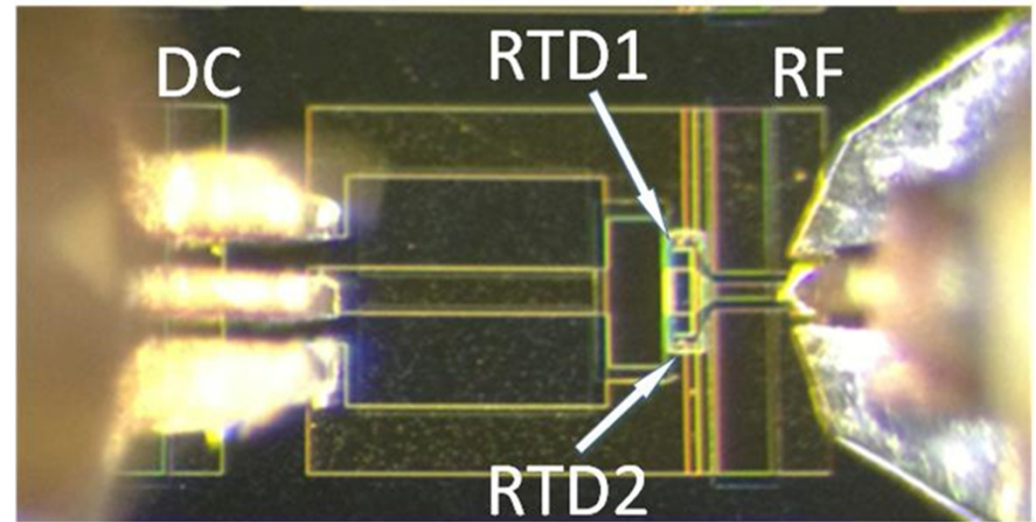
- Monolithic realisation of high power sources
 - 10 mW @ 90 GHz
 - 5 mW @ 160 GHz
 - 1 mW @ 300 GHz
 - Low phase noise sources→ Ultimately on a III-V on Si platform
- **Other iBROW tasks**
 - RTD photodetectors with high responsivity and sensitivity
 - Evaluation of wireless-wireless links and optical-wireless links
 - Test bed demonstrator



2-RTD oscillator layout

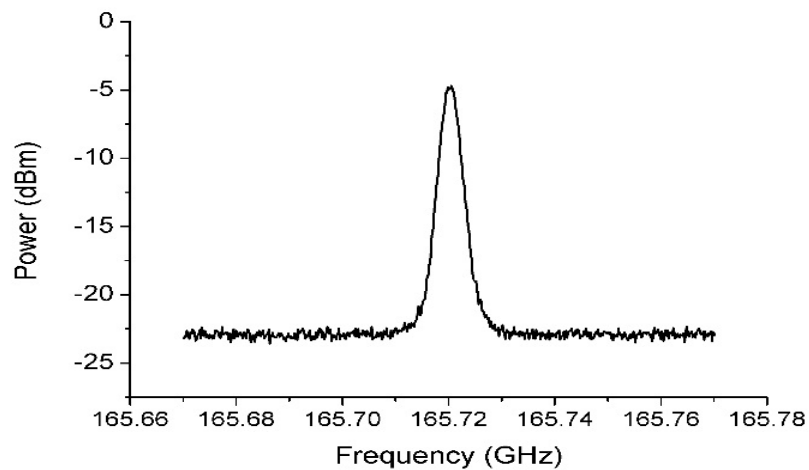


165 GHz oscillator

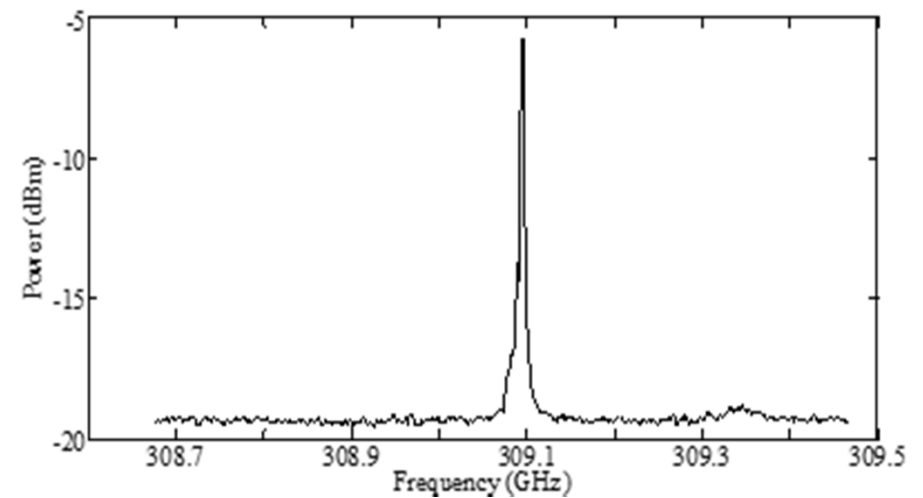


300 GHz^z oscillator

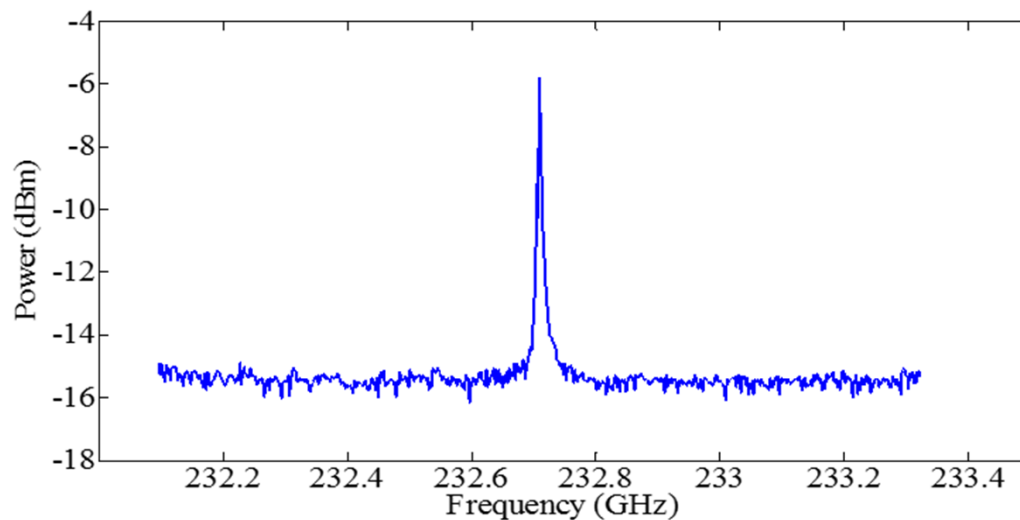
Measured spectra examples



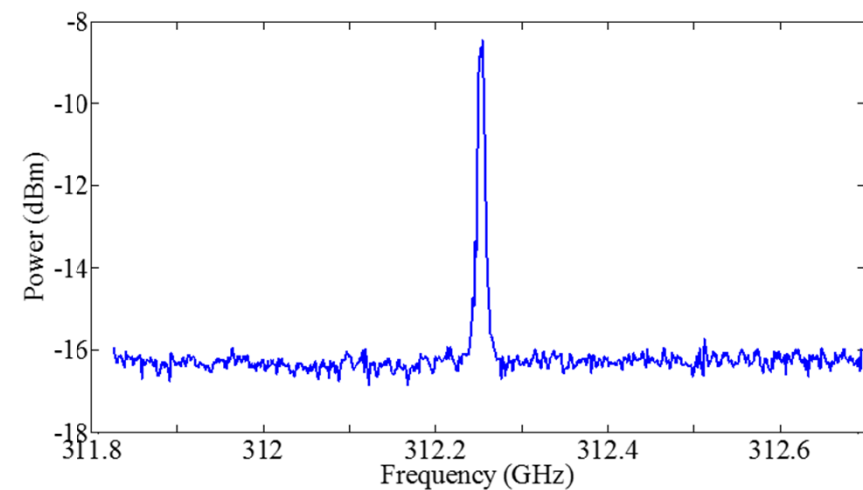
oscillator



309 GHz RTD oscillator

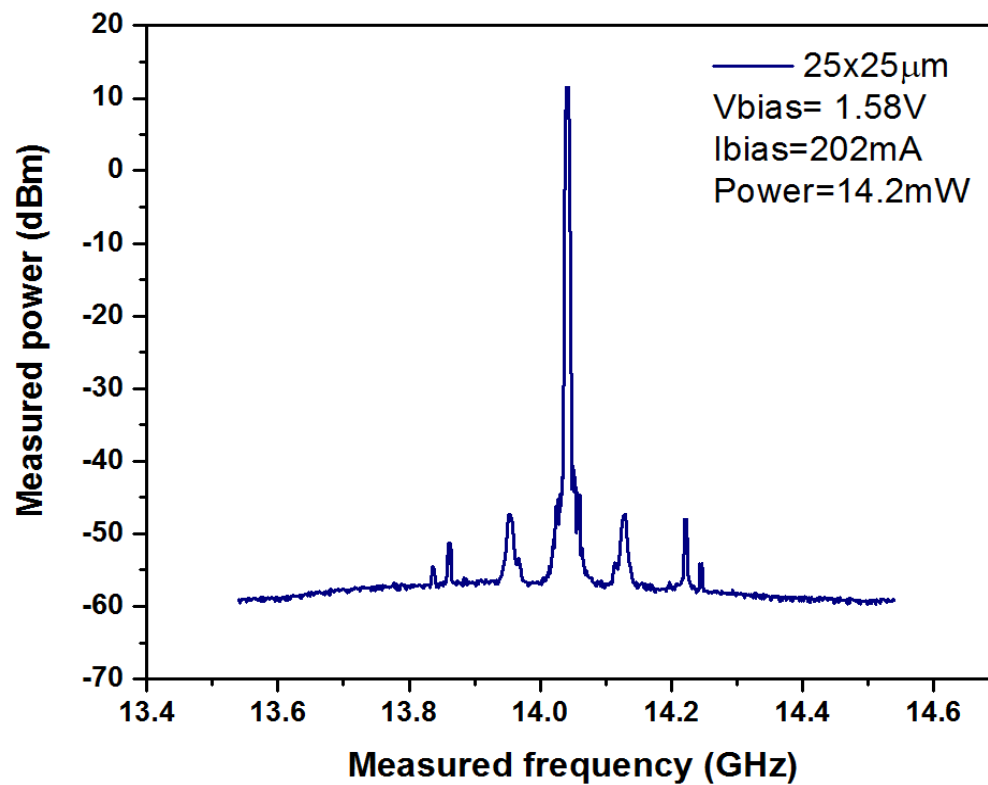


232 GHz RTD oscillator

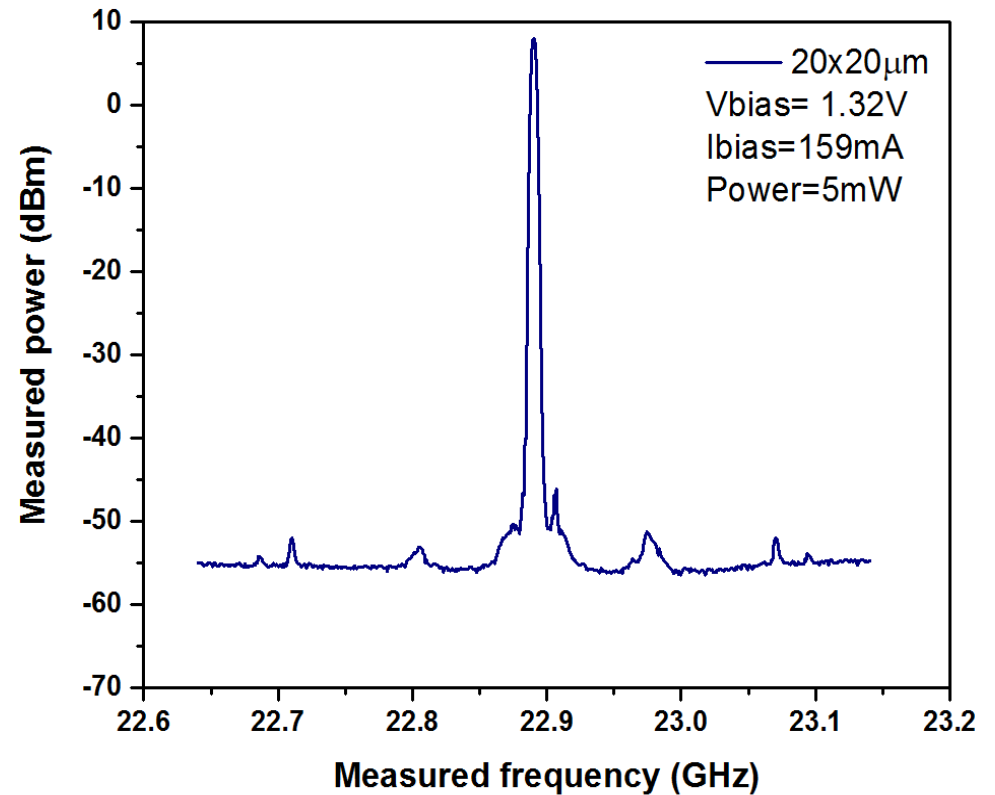


312 GHz RTD oscillator

High power RTD-PD oscillators



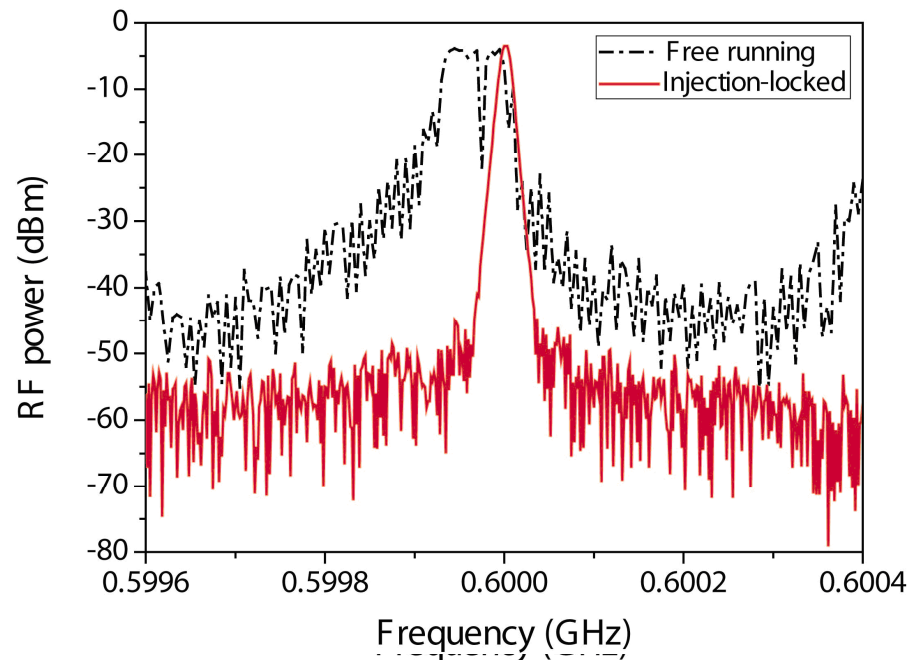
14.2 mW @ 14 GHz



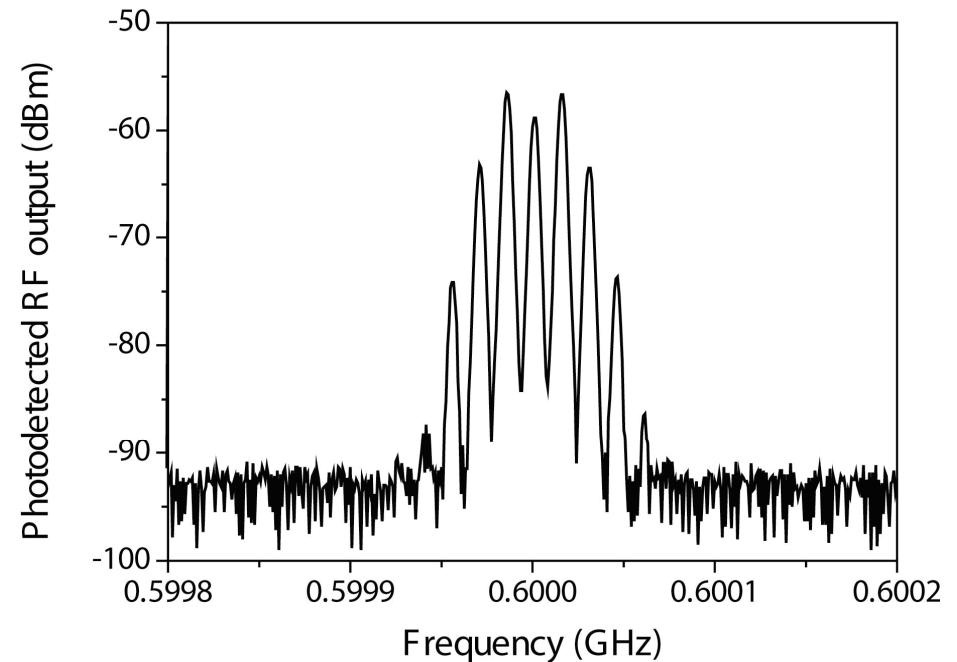
5 mW @ 23 GHz

- The photo-generated current is amplified by the NDR
- Optical locking of the RTD oscillations

Optical injection locking

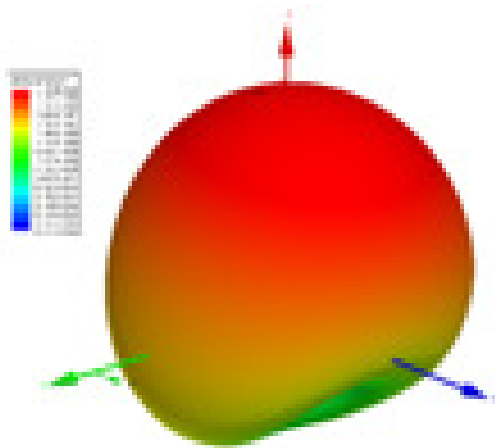
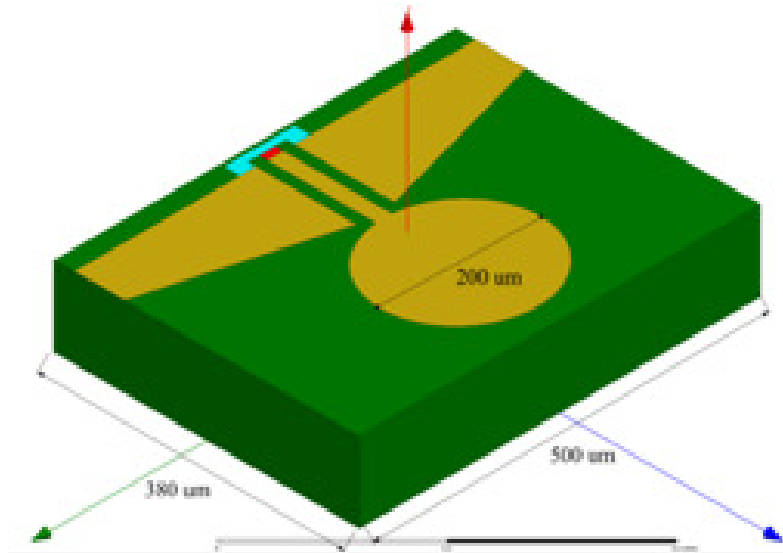


Optical phase-locking

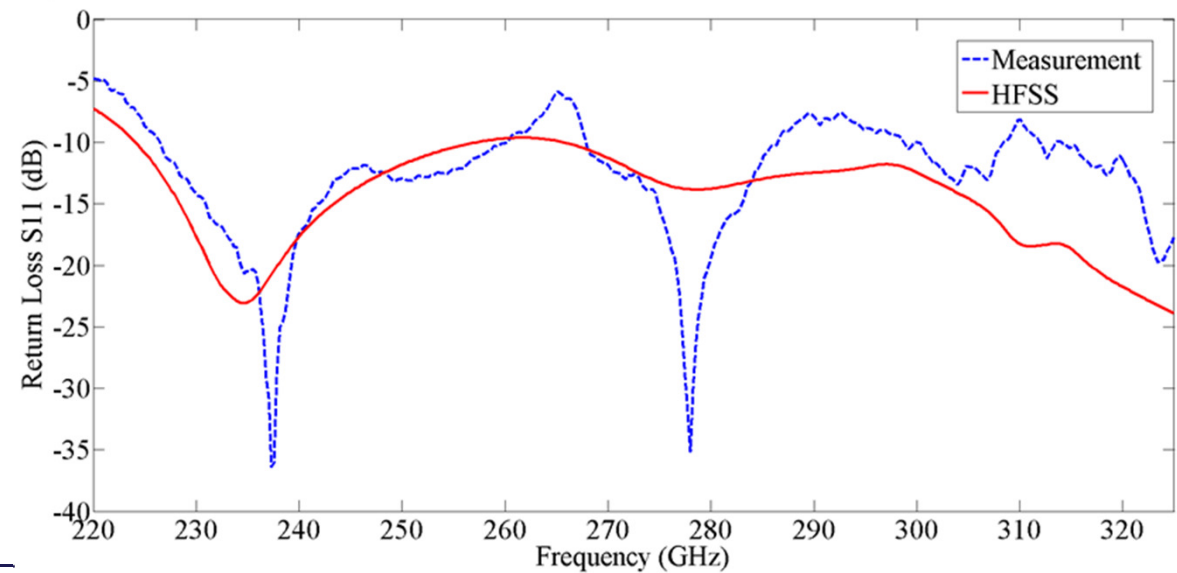
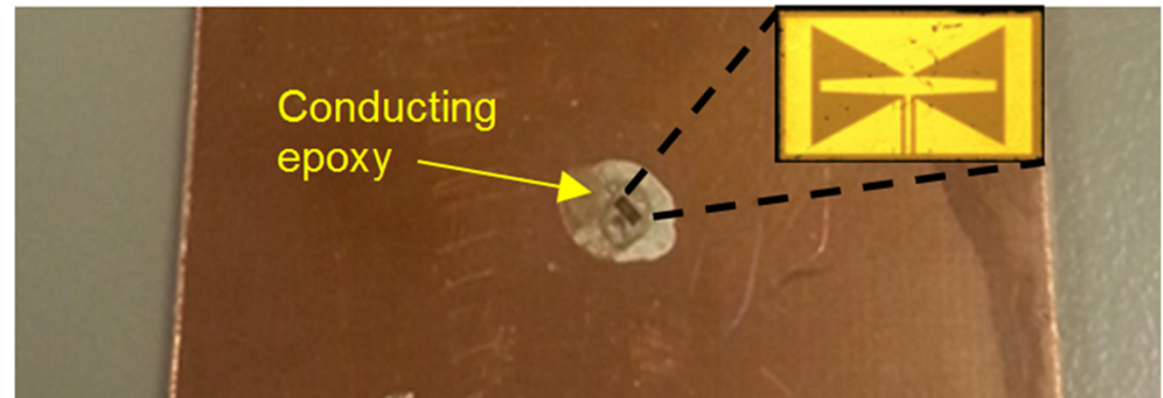


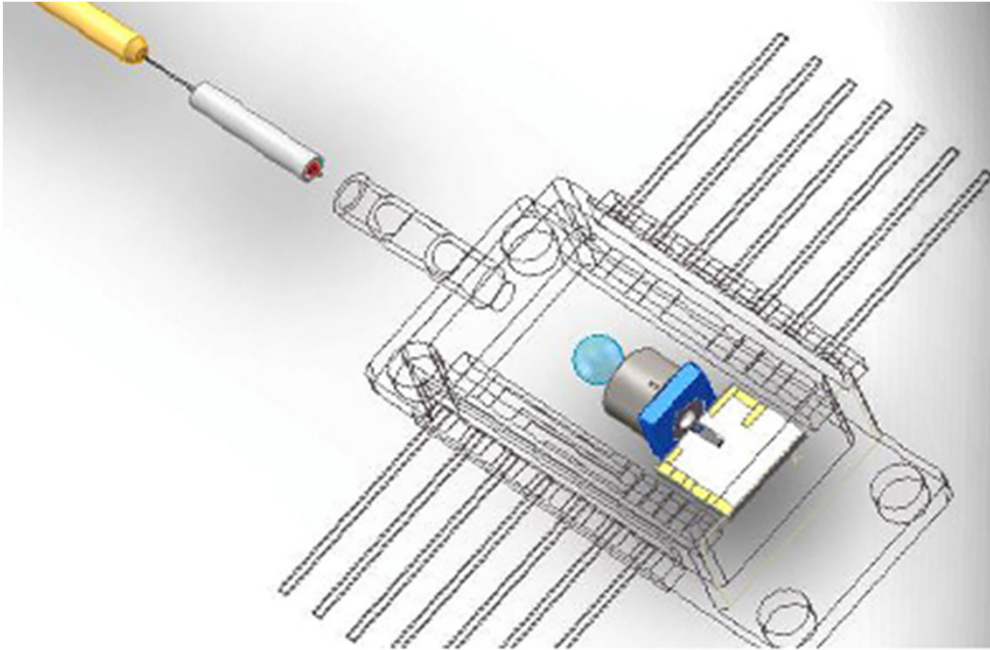
- RTD-PD oscillations follow the phase of the RF optical sub-carrier signal
- This behavior was demonstrated in digital communication schemes including PSK digital modulation *e.g.* RZ-DPSK.

Monopole antenna



Diced and ground slot bow-tie with tuning stub



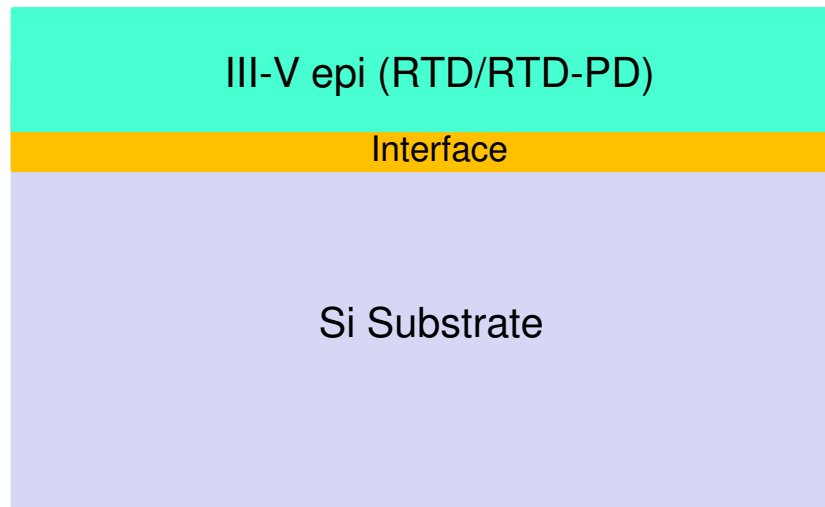


- **Thermal, mechanical and optical packaging design**
- Hermetic sealing
- Lensed fibre coupling

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How to achieve low cost?




III-V on silicon



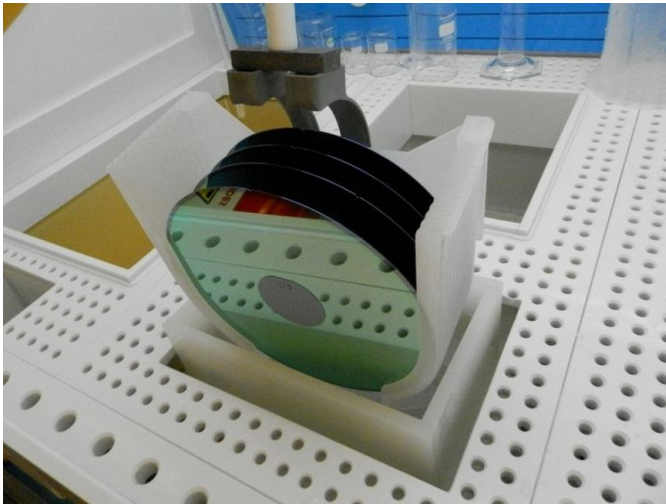
- **Direct growth** of III-V RTD layers on a Si substrate
- **Direct wafer bonding** between III-V & Si substrates
 - Potential for large diameter ≥ 200 mm wafers
 - Integration with CMOS, etc.



III-V on silicon

- Conventional hybrid approaches:
 - Wire-bonded or flip-chip multi-chip assemblies
 - Suffer from variability and relative placement restrictions
- **Direct hetero-epitaxial growth**
 - III-V on a GeOI/Si template
 - Exploit previous knowledge from the DARPA COSMOS programme
- **Direct wafer bonding**
 - Process III-V surface to achieve bonding at room temperature
- Proved effective in solving mismatch problems
 - Lattice constant
 - Thermal expansion coefficient.

III-V on Si: Wafer bonding



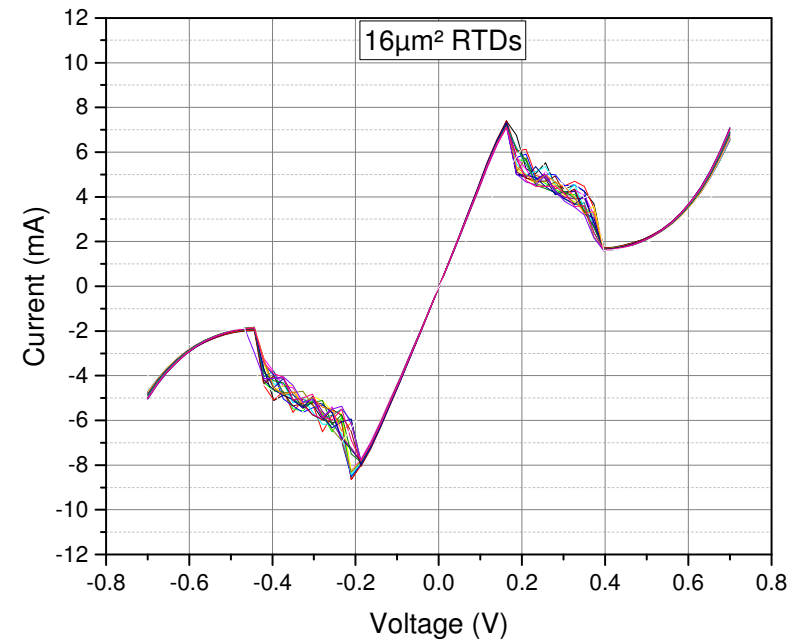
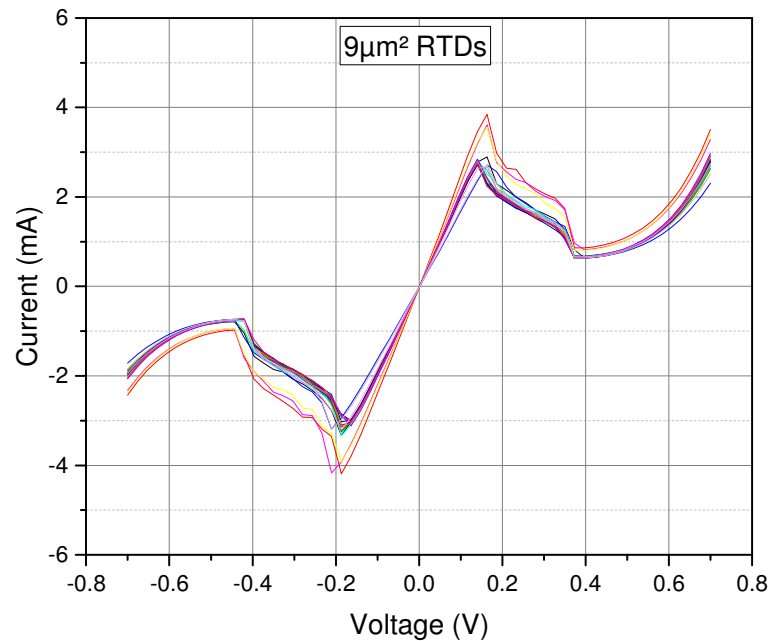
Bath in vertical position



Wafer before and after InP etching



- RTD epitaxial layer structure transferred to a Si host substrate via wafer bonding and subsequent InP removal
- 75 mm wafers obtained by laser dicing



Device characteristics of RTDs on Si

- High fabrication yield
- Clear NDR in forward as well as in reverse bias

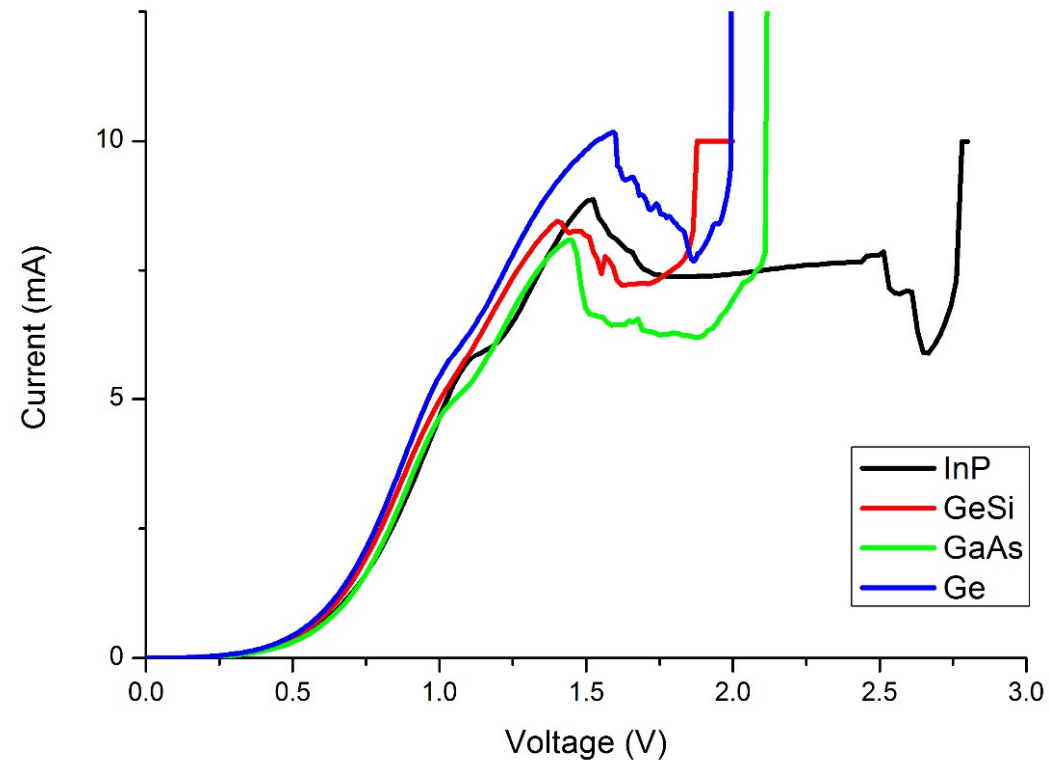
III-V on Si: direct growth



RTD surface on InP substrate,
roughness ~ 2.4 nm

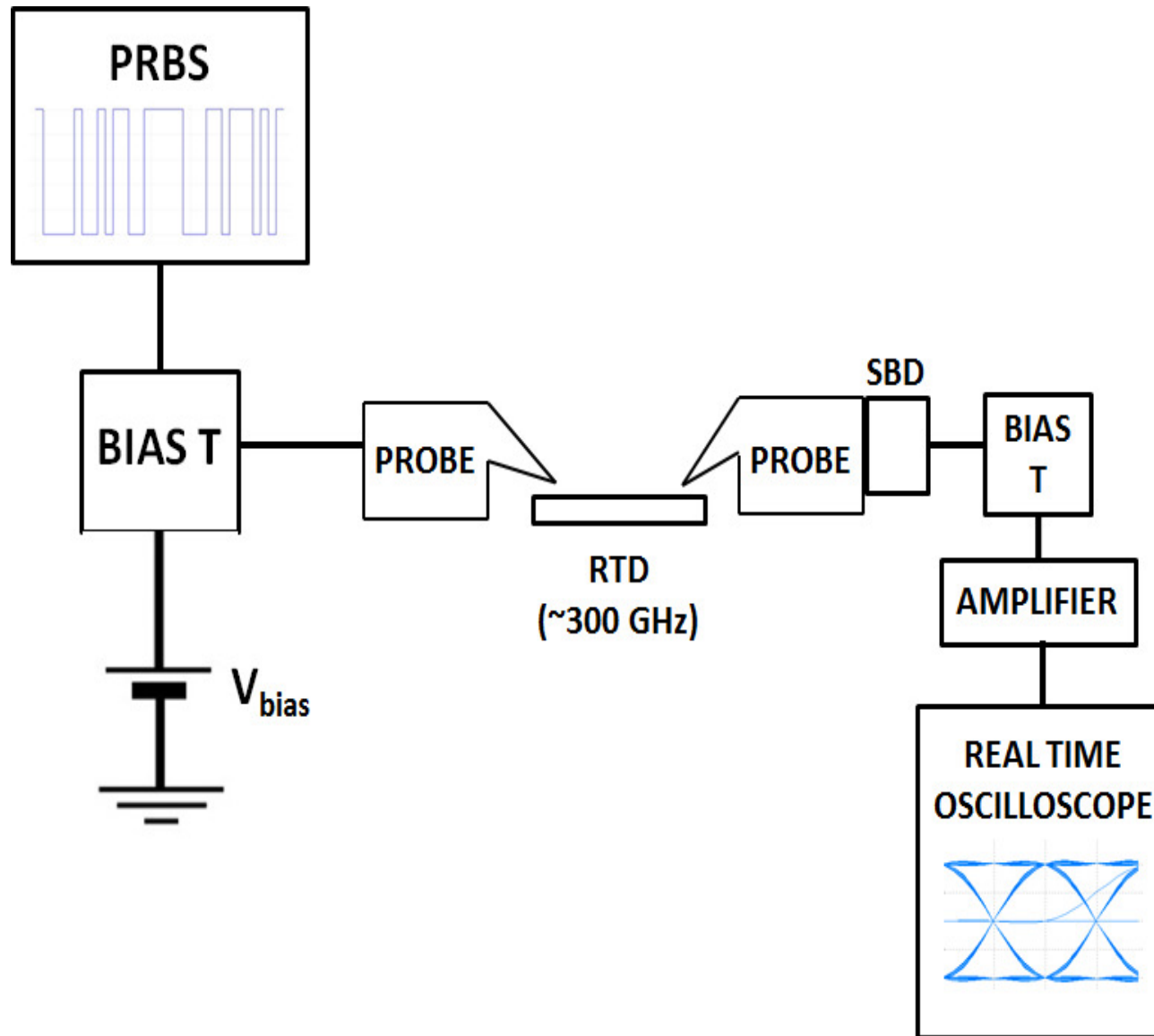


RTD surface on Ge/Si substrates,
roughness ~ 7 nm

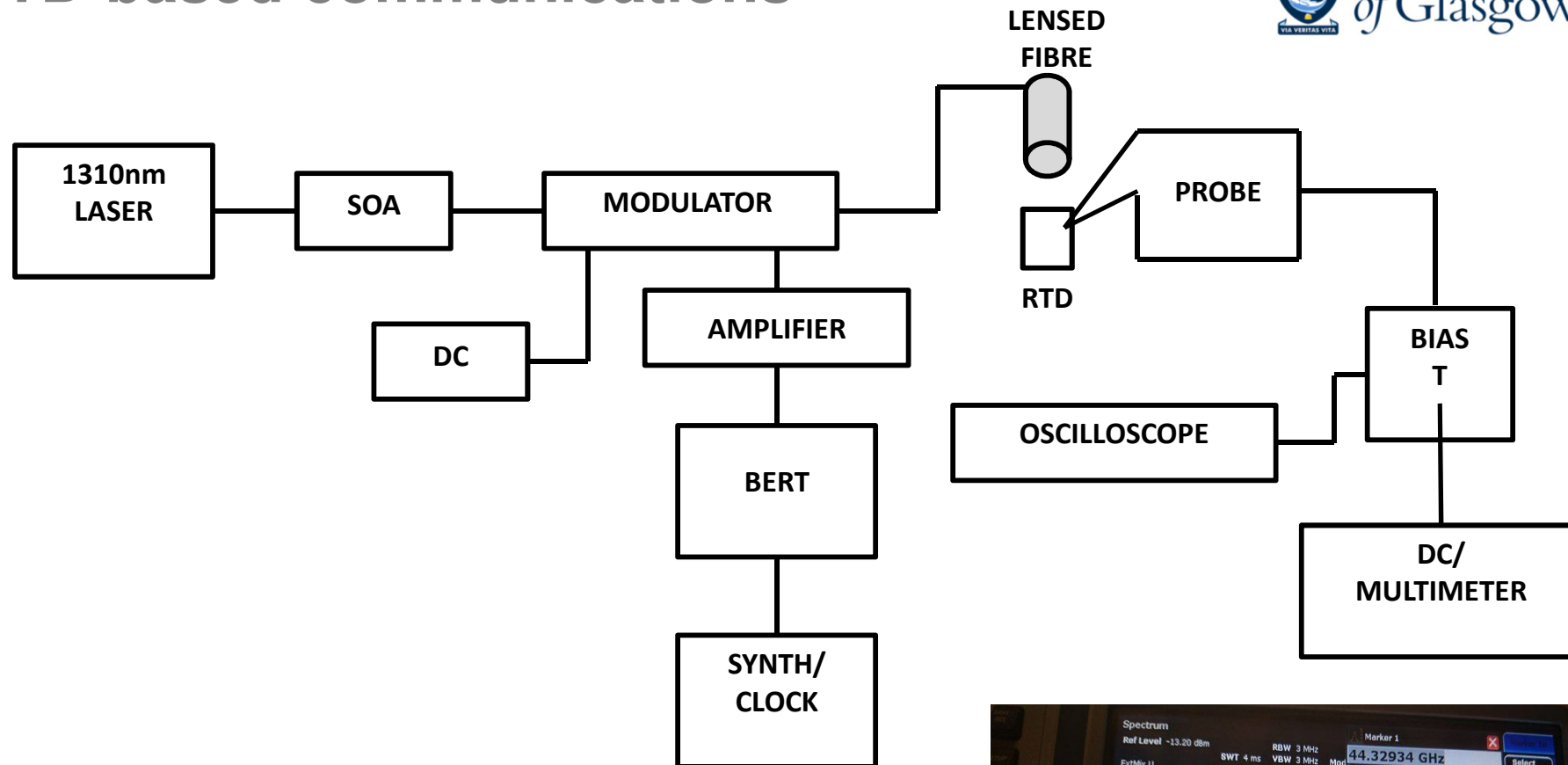


Device characteristics of $9 \mu\text{m}^2$
devices on InP, GaAs, Ge, and Ge-
Si substrates

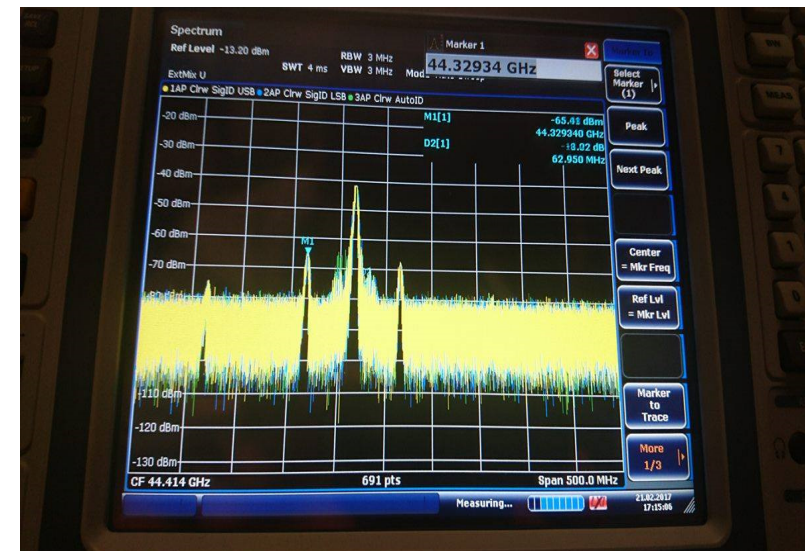
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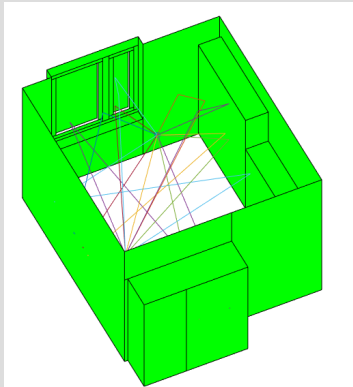
- Data transmission can be achieved using an electronic RTD oscillating at ~300 GHz
- A data pattern can be combined with a DC bias and sent to the RTD
 - Signal can be detected using a Schottky barrier diode (SBD) connected to a high speed probe
- Eye diagrams can be captured to show a visual representation of the received data pattern



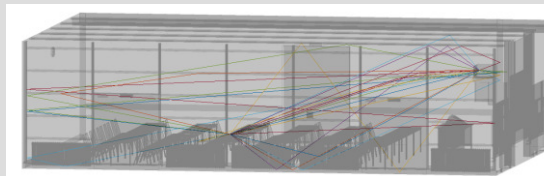
- RTD-PDs can be used as optical data photo-detectors
 - Data can be viewed as eye diagrams
- RTD-PD oscillators react to optical data signal
 - The signal can be used to move the RTD in and out of NDR
 - It can also directly modulate the RTD



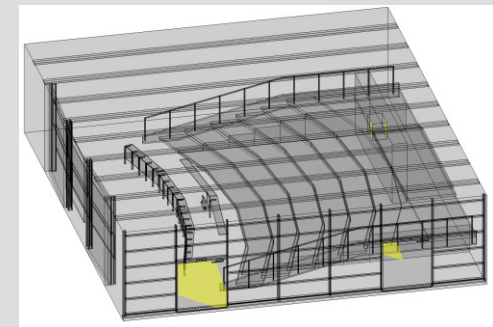
Small Office



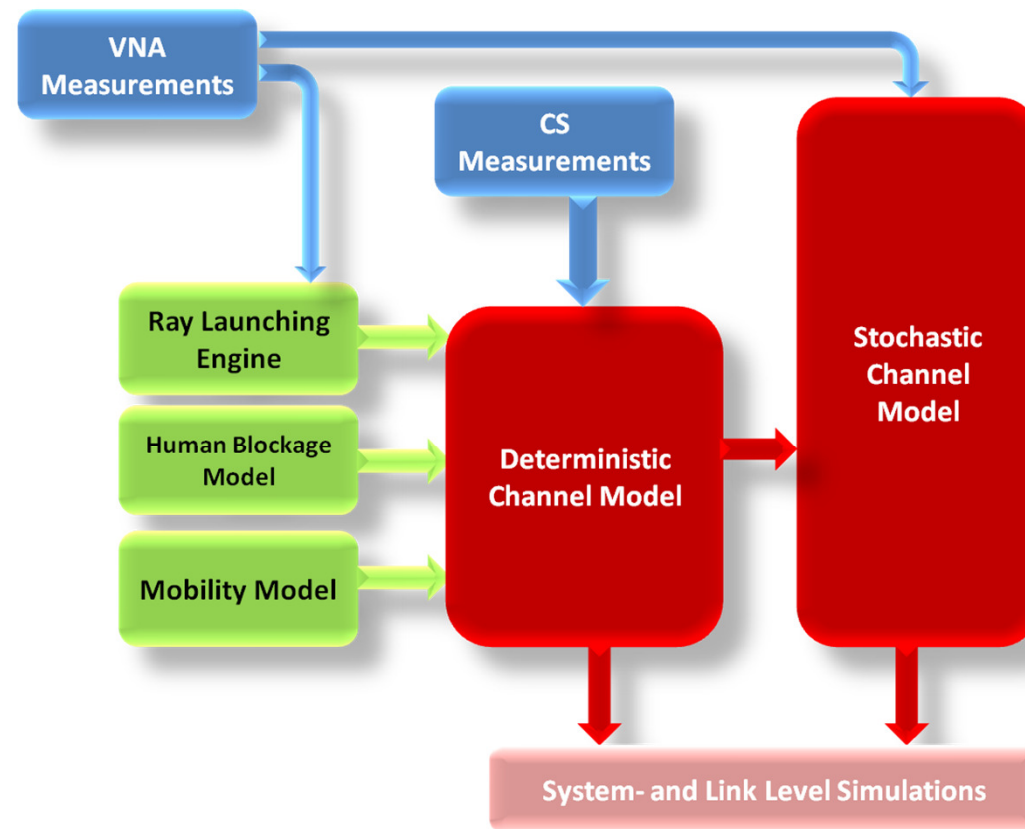
Lecture Hall



Auditorium



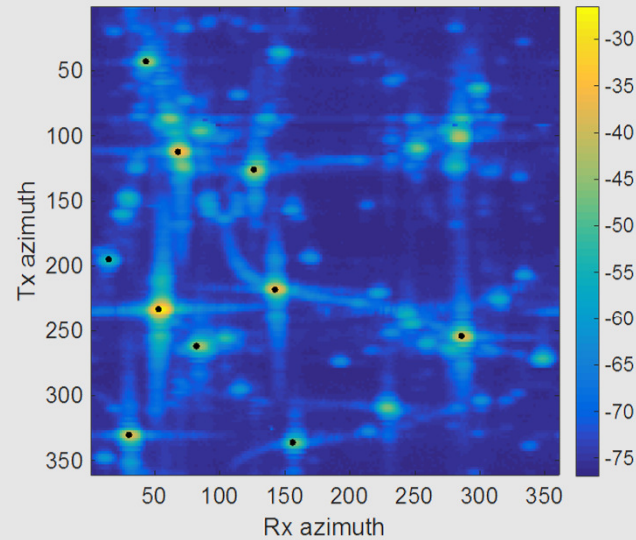
NOKIA Bell Labs



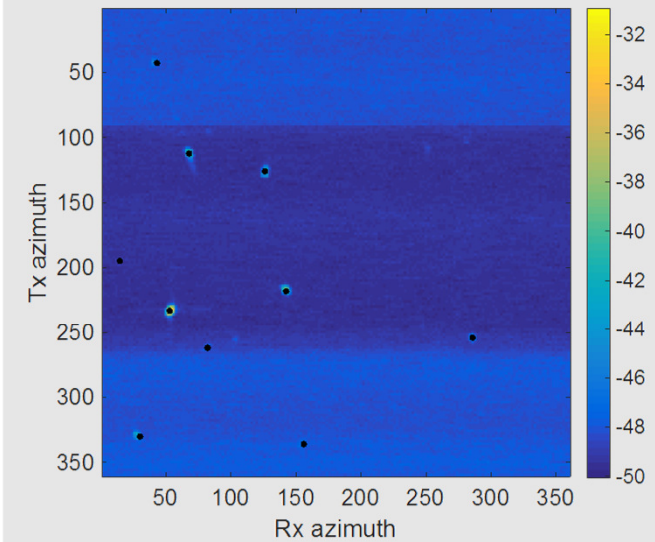
- Channel modelling
- Test-bed for the demonstration of >10 Gbps wireless communications
- Several stand-alone prototype nodes at around 90 GHz and 300 GHz

Spatial Characteristics

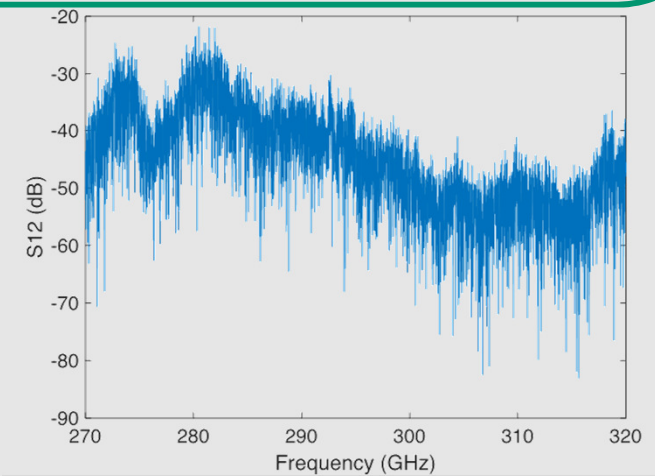
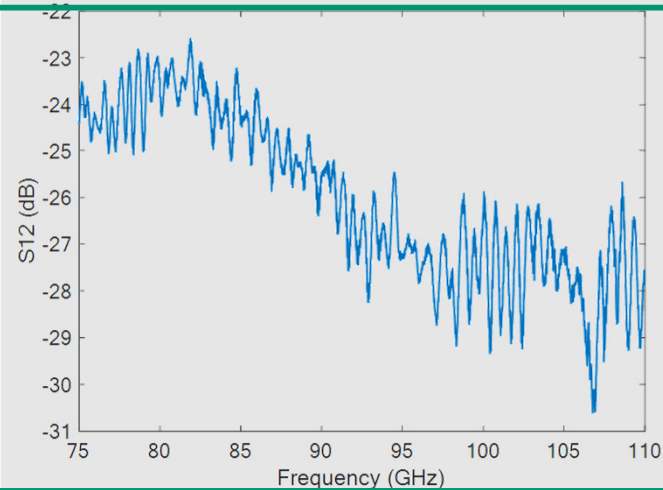
90 GHz band



300 GHz



Transfer Function



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iBROW will achieve a novel RTD device technology:

- On a III-V on Si platform
- Operating at mm-wave and THz frequencies
- Integrated with laser diodes and photo-detectors

A simple technology that can be integrated into both ends of a wireless link

- Consumer portable devices
- Fibre-optic supported base-stations.

- RTD oscillators up to 300 GHz with >1 mW output power demonstrated
- Opto-RTD oscillators with record output power of >10 mW at X-band demonstrated
- III-V (RTD) on Si approaches
- Low-cost high bandwidth THz transceiver technology